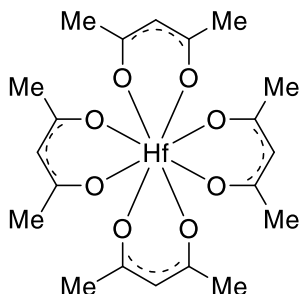


Catalog # 72-2002 Hafnium(IV) acetylacetonate, min. 96%



Thermal Behavior:

- Melting point: 188-190°C [1]
- TGA data and diagram is available in [2]

Technical Notes:

1. Used for the hafnium thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
HfO ₂	CVD	180°C	0.15 Torr	O ₂	490-900°C	3
	LA-CVD	180°C	0.15 Torr	O ₂	600-1300°C	3
	LA-CVD	220°C	0.15 Torr	-	977-1327°C	4
LaHfO _x	CVD	200°C	4.0 Torr	O ₂	600-700°C	5

References:

1. [J. Phys. Chem. Solids, 2008, 69, 673.](#)
2. [J. Therm. Anal. Cal. 2008, 92, 729.](#)
3. [Ceram. Int. 2020, 46, 1810.](#)
4. [RSC Adv. 2022, 12, 15555.](#)
5. [Appl. Surf. Sci. 2010, 256, 2496.](#)